

Z - BEXPRESS Mail No. ER074143390US Attorney Docket No.: AM-8472

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Sang H. Ahn et al.

§ GROUP ART UNIT: Unknown

SERIAL NO.: 10/724,454

S EXAMINER: Unknown

FILED: November 28, 2003

EXAMINER: Unknown

FOR: MAINTENANCE OF PHOTORESIST ADHESION

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§ Attorney Docket No.:

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AM-8472

Date: December 16, 2003

INFORMATION DISCLOSURE STATEMENT TRANSMITTAL LETTER

Hon. Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Sir:

Applicants are submitting the subject Information Disclosure Statement under 37 CFR § 1.97(b)(1). This Information Disclosure Statement is being submitted within three (3) months of the filing date of the subject application.

CERTIFICATE OF MAILING UNDER 37 CFR § 1.10

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. ER074143390US in an envelope addressed to: Mail Stop DD, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Date: December 16, 2003

Shirley L. Church, Reg. No. 31,858

Applicants do not believe that any fee is due in connection with the filing of this Information Disclosure Statement under 37 CFR § 1.97(b)(1). However, in the event that any additional fee is due, the Commissioner is hereby authorized to charge Deposit Account No. 50-1512 of Shirley L. Church, Sunnyvale, California, in the amount of such fee.

This transmittal letter is submitted in duplicate for accounting purposes.

Respectfully submitted,

Shirley L. Church

Registration No. 31,858 Attorney for Applicants

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FORM PTO-1449 (Equivalent) U.S. Department of Commerce Patent and Trademark Office

U.S. Application Serial No. 10/724.454

Atty. Docket No.

AM-8472



INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

Sang H. Ahn et al. Applicants

November 28, 2003 Filing Date

<u>Unknown</u> Group

			U.S.	PATENT DOCUMI	ENTS		
Examiner Initial	Document Number	Issue <u>Date</u>		Name	Class	Subclass	Filing Date If Appropriate
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	2003/00875	18 A1 05	/08/03	Chen et al.	438	637	11/08/01

Examiner Date Considered

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FOREIGN PATENT DOCUMENTS

Examiner <u>Initial</u>	Document Number	Publication <u>Date</u>	Name	Class	Subclass	Translation If Appropriate
	EP 1011135	06/21/00	Hsia et al.	H01L	21/768	
	WO 01/09683	02/08/01	Lee et al.	G03F	7/09	
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